

ABSTRACT OF DISCLOSURE

ETCH MASK

Provided is a etch mask that prevents the separation of the etch mask which occurs in the
5 vicinity of an end portion of a material to be etched during etching step. The etch mask is one formed on a surface of a material to be etched and comprising collected linear masks. A portion of a linear mask positioned in the vicinity of an end portion of the material to be etched becomes a wider portion as compared with the remaining portion or a zigzag portion. As required, the middle portion of the linear mask also becomes a wider portion or a zigzag portion.

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